ABSTRACT

Disclosed are a substrate cleaning device and a wet processing apparatus. The substrate cleaning device comprises a nozzle and a swing arm, the nozzle is disposed at one end of the swing arm, a first fluid tube is disposed in the inner cavity of the swing arm, the first fluid tube is in communication with the nozzle for supplying a first fluid to the nozzle, the outer surface of the tube wall of the first fluid tube is covered with a heating film layer, and the heating film layer is used to transfer heat to the first fluid through the tube wall of the fluid tube, so that the temperature of the first fluid reaches the target temperature. The first fluid can be heated to an ultra-high temperature to meet process requirements.